

AMENDMENTS TO THE CLAIMS

Please amend the claims as indicated in the following listing of all claims:

1. (Canceled)
2. (Previously presented) The apparatus, as recited in claim 23, wherein the aperture is substantially parallel to a plane of current flow in the inductor.
3. (Canceled)
4. (Previously presented) The apparatus, as recited in claim 23, wherein the plurality of electrically conductive links reduce an effect of electromagnetic signals external to the electrically conductive enclosure on the inductor.
5. (Currently amended) The apparatus, as recited in claim 23, wherein the plurality of electrically conductive links and the at least one additional electrically conductive link reduce coupling in the inductor from external sources by approximately 6dB.
6. (Currently amended) The apparatus, as recited in claim 23, wherein each of the plurality of electrically conductive links and the at least one additional electrically conductive link are approximately 5 μ m wide.
7. (Currently amended) The apparatus, as recited in claim 23, wherein the plurality of electrically conductive links and the at least one additional electrically conductive link are formed in one or more traditional integrated circuit layers.
8. (Previously presented) The apparatus, as recited in claim 23, wherein the electrically conductive enclosure includes a top plate, a bottom plate, and sidewalls.
9. (Canceled)

10. (Original) The apparatus, as recited in claim 8, wherein the aperture is formed in the bottom plate.

11. (Original) The apparatus, as recited in claim 8, wherein the bottom plate is formed in one or more integrated circuit metal layers.

12. (Original) The apparatus, as recited in claim 8, wherein the top plate is formed in a metal layer.

13. (Original) The apparatus, as recited in claim 8, wherein the top plate is formed in a redistribution layer.

14. (Original) The apparatus, as recited in claim 8, wherein the top plate is formed in a package substrate.

15. (Previously presented) The apparatus, as recited in claim 23, wherein the inductor is formed at least partially in one or more metal layers of an integrated circuit die thicker than others of the metal layers.

16. (Previously presented) The apparatus, as recited in claim 23, wherein the inductor is formed at least partially in one or more redistribution layers formed on an integrated circuit die.

17. (Previously presented) The apparatus, as recited in claim 23, wherein the inductor is formed on an integrated circuit die.

18. (Original) The apparatus, as recited in claim 17, wherein a conductor forming the inductor is 10 μ m wide.

19. (Original) The apparatus, as recited in claim 17, wherein the aperture and the inductor are effectively spaced at least 10.25 μ m apart.

20. (Canceled)

21. (Canceled)

22. (Canceled)

23. (Currently amended) An apparatus comprising:
an inductor;
an electrically conductive enclosure electromagnetically shielding the inductor, the
electrically conductive enclosure having an aperture at least as large as the
inductor, the aperture being substantially centered around a projected surface of
the inductor; and

a plurality of electrically conductive links, individual ones of the plurality of electrically
conductive links extending across the aperture; and
at least one additional electrically conductive link,

wherein the plurality of electrically conductive links are electrically coupled to the
electrically conductive enclosure and are electrically coupled to each other at a
first location within the aperture, and

wherein individual ones of the plurality of electrically conductive links are coupled to
each other at least at a second location within the aperture by an the at least one
additional electrically conductive link, the at least one additional electrically
conductive link being within the aperture.

24-45. (Canceled)

46. (Previously Presented) The apparatus, as recited in claim 23, wherein the aperture is
formed in an electrically conductive plate of the electrically conductive enclosure.

47-54. (Canceled)

55. (Previously presented) The apparatus, as recited in claim 23, wherein the aperture
has an approximate diameter determined by adding an approximate outer diameter of the
inductor to an approximate inner diameter of the inductor.

56. (Currently amended) The apparatus, as recited in claim 23, wherein the at least one additional electrically conductive link within the aperture intersects each of the individual ones of the plurality of electrically conductive links at ninety degree angles.

57. (Previously presented) The apparatus, as recited in claim 23, wherein the first location is in the center of the aperture and the second location is between the center of the aperture and the perimeter of the aperture.

58. (New) The apparatus, as recited in claim 23, wherein individual ones of the plurality of electrically conductive links are coupled to at least one portion of the electrically conductive enclosure at a third location, the third location being at the perimeter of the aperture.